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Attorney Docket No. 5038-062725

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No. : Not Yet Assigned  
Applicants : **Ho-Seong NAM et al.**  
Filed : Concurrently Herewith  
Title : **CHEMICAL MECHANICAL POLISHING  
SLURRY COMPOSITION FOR SHALLOW  
TRENCH ISOLATION PROCESS OF  
SEMICONDUCTOR**  
International Application No. : PCT/KR2005/000859  
International Filing Date : 24 March 2005  
Priority Date(s) Claimed : 29 March 2004

**MAIL STOP PCT**  
Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

**PRELIMINARY AMENDMENT**

Sir:

Prior to initial examination, please amend the above-identified patent application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 1 of this paper.

**Amendments to the Abstract** begin on page 5 of this paper and a replacement page is attached hereto.

**Remarks** begin on page 6 of this paper.